Docket No.: 53074-026

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Tetsuzo Ueda

Serial No.: 09/904,131

Filed: July 11, 2001

MAR 1 7 2003 W

Group Art Unit: 1765

Examiner: Matthew Song

LAYERED SUBSTRATES FOR EPITAXIAL PROCESSING AND DEVICE

THE COMMISSIONER FOR PATENTS AND TRADEMARKS Washington, DC 20231

Dear Sir:

For:

<u>Transmitted</u> herewith is an Amendment in the above identified application.

No additional fee is required.

Applicant is entitled to small entity status under 37 CFR 1.27

Also attached:

The fee has been calculated as shown below:

	NO. OF CLAIMS	HIGHEST PREVIOUSLY PAID FOR	EXTRA CLAIMS	RATE	FEE
Total Claims	18	23	0	\$18.00 =	\$0.00
Independent Claims	4	7	0	\$84.00 =	\$0.00
7		Multiple claims newly presented			\$0.00
	Fee for extension of time				\$0.00
					\$0.00
		Total of Above Calculations		\$0.00	

Please charge my Deposit Account No. <u>500417</u> in the amount of \$0.00. An additional copy of this transmittal sheet is submitted herewith.

The Commissioner is hereby authorized to charge payment of any fees associated with this communication or credit any overpayment, to Deposit Account No. 500417, including any filing fees under 37 CFR 1.16 for presentation of extra claims and any patent application processing fees under 37 CFR 1.17.

Respectfully submitted,

MCDERMOTT, WILL & EMERY

#46,692

Michael E. Fogarty Registration No. 36,139

600 13<sup>th</sup> Street, N.W. Washington, DC 20005-3096 (202) 756-8000 MEF:RMF:amz

Facsimile: (202) 756-8087 **Date: March 17, 2003** 

**PATENT** 

Docket No.: 53074-026

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Tetsuzo Ueda

Serial No.: 09/904,13

Filed: July 11, 2001

Group Art Unit: 1765

Examiner: Matthew Song

For: LAYERED SUBSTRATES FOR EPITAXIAL PROCESSING AND DEVICE

## **AMENDMENT**

Commissioner for Patents Washington, DC 20231

Sir:

In response to the Office Action dated January 6, 2003, having a three-month shortened statutory period for response set to expire on April 6, 2003, reconsideration of the above-identified application is respectfully requested in view of the following amendment and remarks.

## **IN THE CLAIMS**

Please amend claims 11, 12, 15, 18 and 19 to read as follows:

11. An epitaxial growth method comprising:

growing an epitaxial layer on a layered substrate which exhibits bowing, wherein the layered substrate has at least two layers, wherein at least two of the layers have different thermal coefficients.

12. The epitaxial growth method of claim 11 further comprising the step of selective etching a portion of the epitaxial layer.